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(71) Applicant: **L'AIR LIQUIDE, SOCIETE ANONYME
POUR L'ETUDE ET L'EXPLOITATION DES PRO-
CEDES GEORGES CLAUDE** [FR/FR]; 75 Quai d'Orsay,
75007 Paris (FR).

(71) Applicant (for US only): **AMERICAN AIR LIQUIDE,
INC.** [US/US]; 46409 Landing Parkway, Fremont, CA
94538 (US).

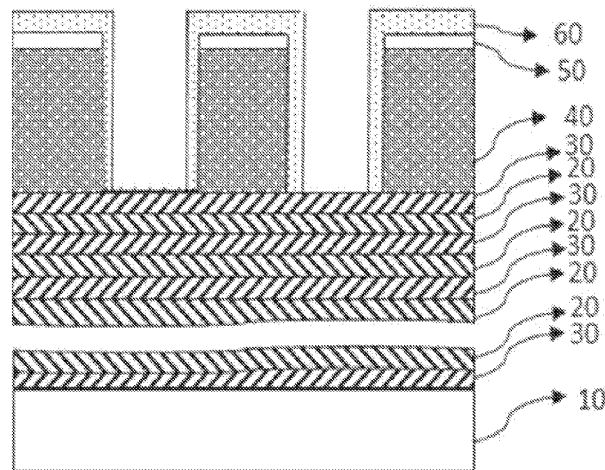
(72) Inventors: **ARTEAGA MULLER, Rocio, Alejandra**;
Hikarinooka 2-2, Yokosuka, Kanagawa, 239-0847 (JP).
GIRARD, Jean-Marc; 75, Quai d'Orsay, 75007 Paris (FR).
GATINEAU, Julien; 75, Quai d'Orsay, 75007 Paris (FR).
PALLEM, Venkateswara, R.; 200 GBC Drive, Newark,
DE 19702 (US).

(74) Agent: **WHITE, Allen, E.**; Air Liquide, 9811 Katy Free-
way, Suite 100, Houston, TX 77024 (US).

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(54) Title: METHOD OF FORMING A RUTHENIUM-CONTAINING LAYER AND LAMINATE

Fig. 1C



(57) Abstract: [Purpose] To provide a method of forming a ruthenium-containing layer and a laminate, wherein the ruthenium-containing layer is selectively formed, as a protective layer capable of suppressing generation of etching residues, on a mask surface for pattern formation that is formed on a substrate, without the need for forming a selective attractant element. [Solution] A method, which comprises a preparation step of providing a substrate having an oxidizable layer, and a deposition step of depositing a ruthenium-containing layer on the oxidizable layer by using a ruthenium tetroxide through vapour deposition, wherein the oxidizable layer contains carbon atoms.

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